



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tsuneo KAGOTANI et al.

Group Art Unit: 3729

Application No.: 10/643,917

Examiner: T. NGUYEN

Filed: August 20, 2003

Docket No.: 116900

For: MAGNETO-RESISTANCE EFFECT ELEMENT BAR EXPOSURE METHOD,
MAGNETO-RESISTANCE EFFECT ELEMENT BAR FORMATION METHOD AND
MAGNETO-RESISTANCE EFFECT ELEMENT BAR

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

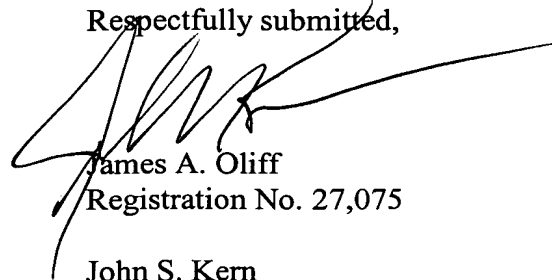
Sir:

In reply to the March 27, 2006 Restriction Requirement, Applicants provisionally elect Group IA, claims 1-3, with traverse.

It is also respectfully submitted that the subject matter of all claims 1-6 is sufficiently related that a thorough search for the subject matter of any one Group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of an entire application can be made without serious burden, the examiner must examine it on the merits, even though it includes claims to independent or distinct inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,



James A. Oliff
Registration No. 27,075

John S. Kern
Registration No. 42,719

JAO:JSK/dxc

Date: April 13, 2006

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

<p>DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461</p>
--